

# EE 330

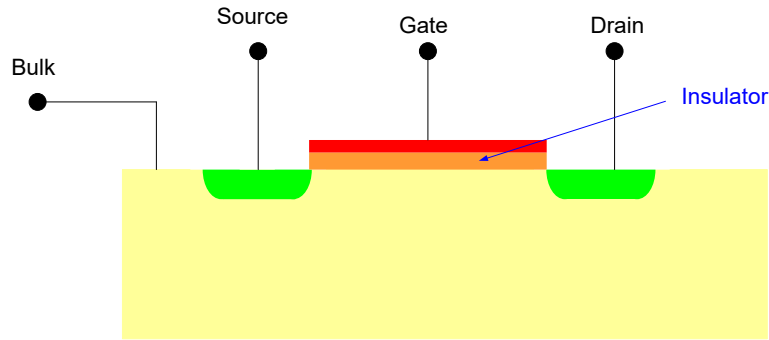
## Lecture 7

- Propagation Delay
- Stick Diagrams
- Technology Files
  - Design Rules

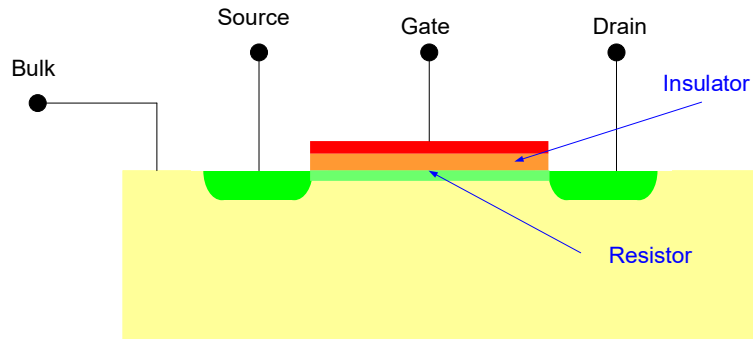
## Review from Last Time

# MOS Transistor

## Qualitative Discussion of n-channel Operation



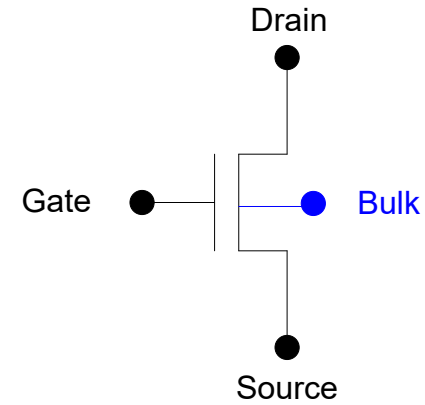
For  $V_{GS}$  small



n-channel MOSFET

For  $V_{GS}$  large

- Region under gate termed the “channel”
- When “resistor” is electrically created, region where it resides in channel is termed an “inversion region”

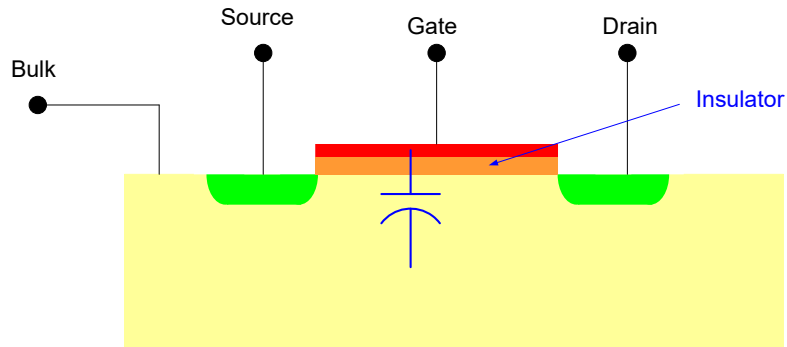


MOSFET actually 4-terminal device

## Review from Last Time

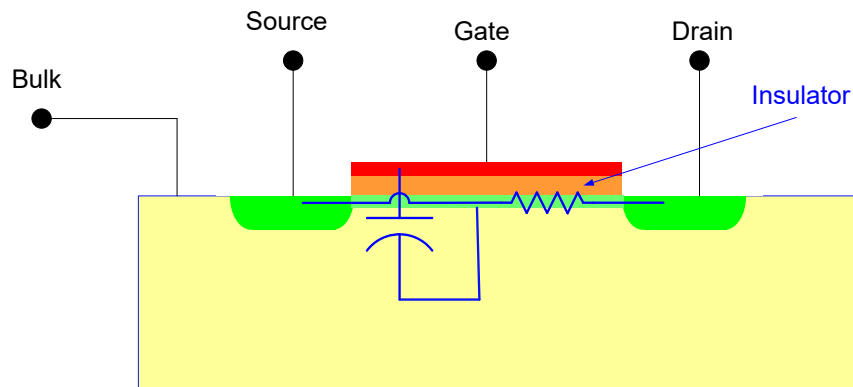
# MOS Transistor

## Qualitative Discussion of n-channel Operation



n-channel MOSFET

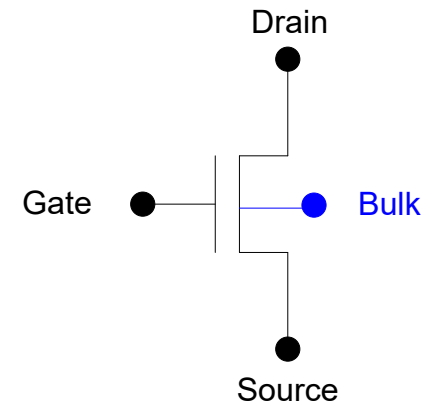
For  $V_{GS}$  small



n-channel MOSFET

For  $V_{GS}$  large

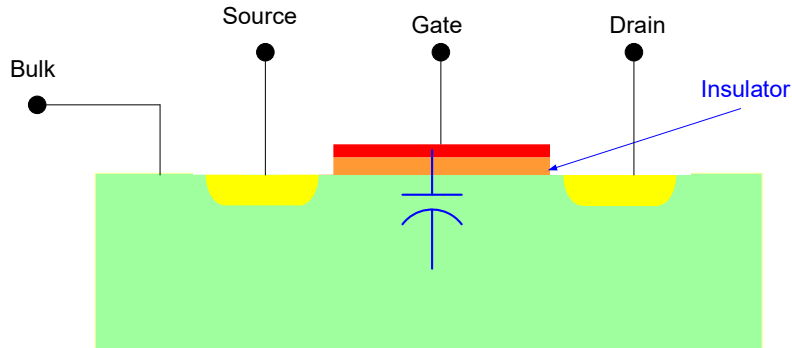
- Electrically created inversion layer forms a “thin “film” resistor
- Capacitance from gate to channel region is distributed
- Lumped capacitance much easier to work with



## Review from Last Time

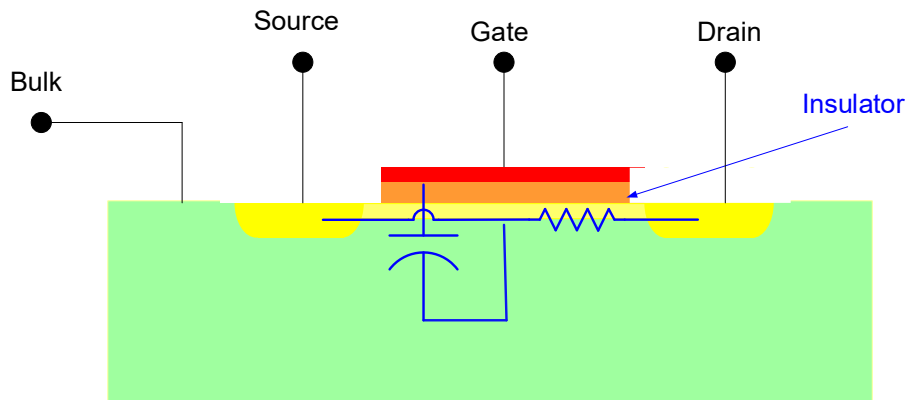
# MOS Transistor

## Qualitative Discussion of p-channel Operation

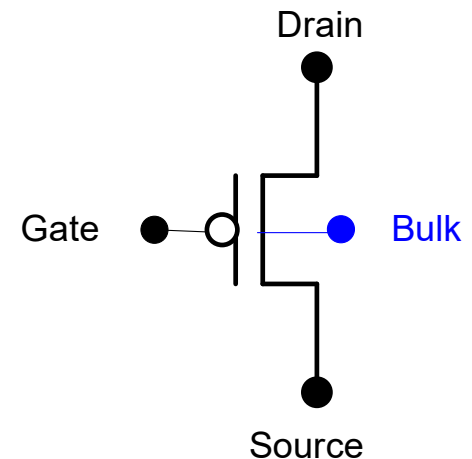


p-channel MOSFET

For  $|V_{GS}|$  small



p-channel MOSFET

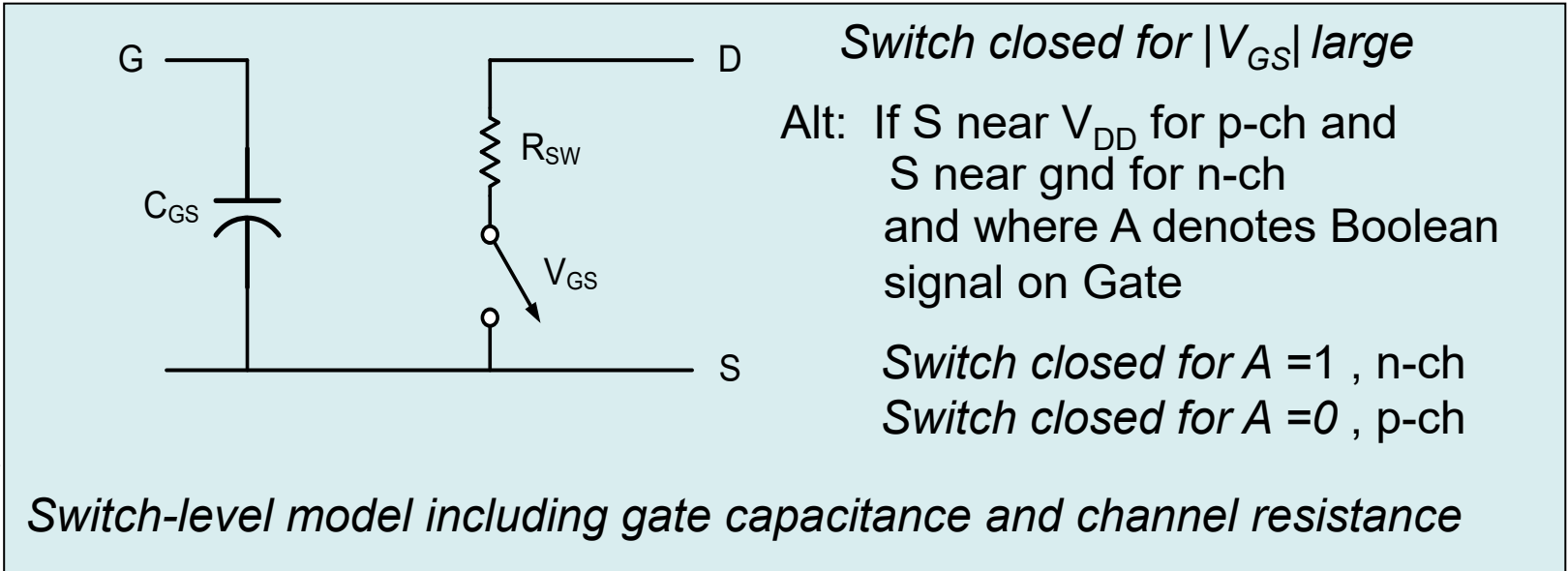
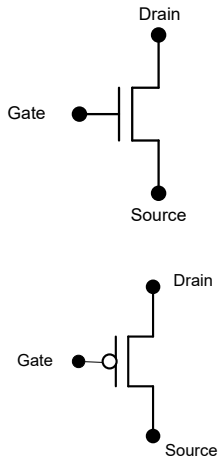


For  $|V_{GS}|$  large

- Electrically created inversion layer forms a “thin “film” resistor
- Capacitance from gate to channel region is distributed
- Lumped capacitance much easier to work with

## Review from Last Time

# Improved Switch-Level Model



*$C_{GS}$  and  $R_{SW}$  dependent upon device sizes and process*

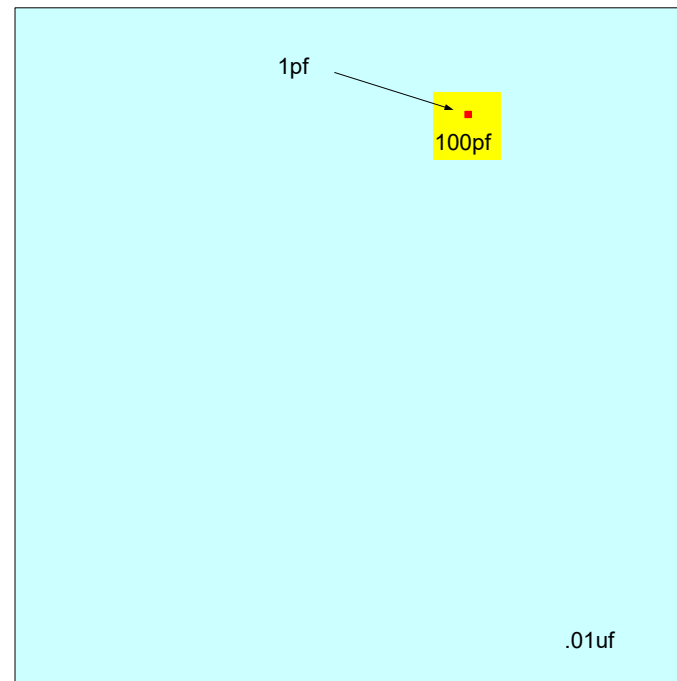
*For minimum-sized devices in a 0.5u process with  $V_{DD}=5V$*

$$C_{GS} \cong 1.5\text{fF} \quad R_{sw} \cong \left. \begin{array}{l} 2\text{K}\Omega \text{ n-channel} \\ 6\text{K}\Omega \text{ p-channel} \end{array} \right\}$$

*Considerable emphasis will be placed upon device sizing to manage  $C_{GS}$  and  $R_{SW}$*

Review from Last Time

# Is a capacitor of 1.5fF small enough to be neglected?



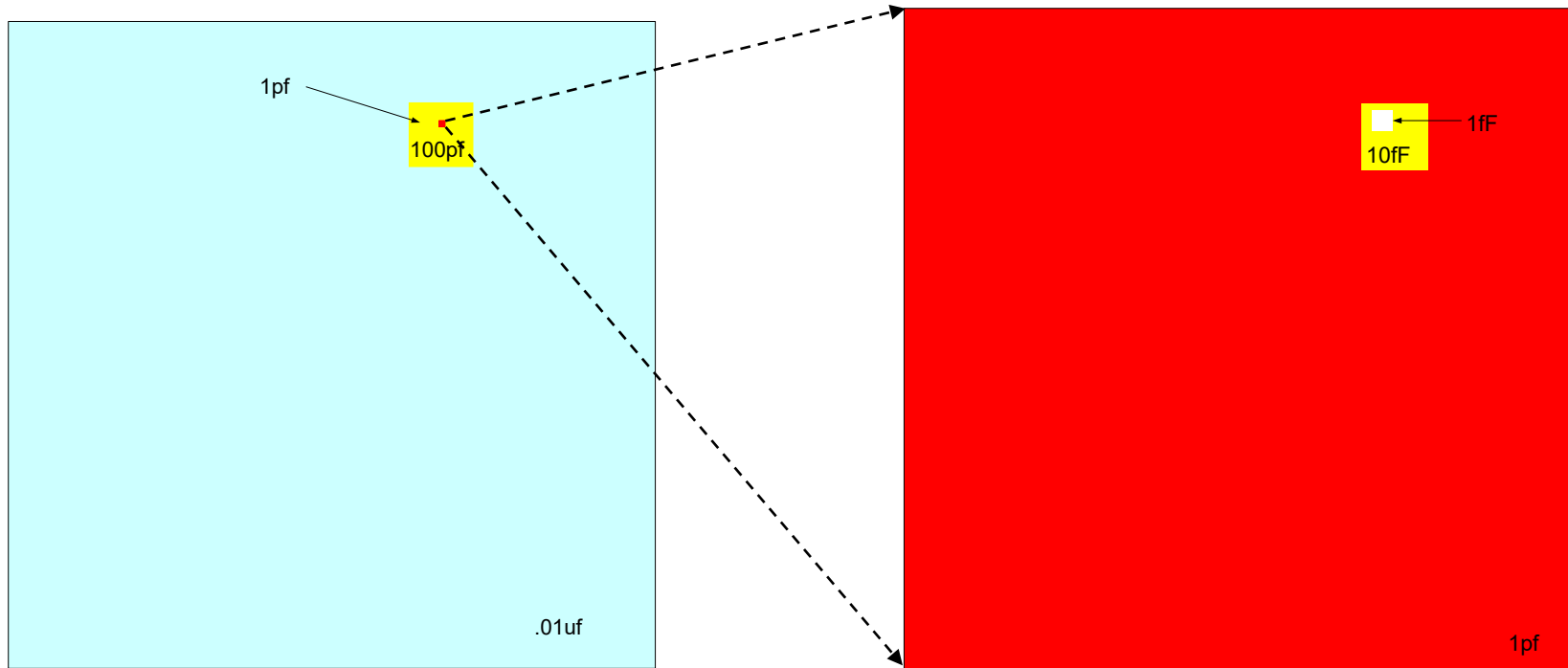
From EE 201 Parts Kit

Capacitors (Farads)		
100p	3	
470p	3	
0.001u	3	2
0.0047u	3	2
0.01u	3	
0.047u	3	
0.1u	3	1
0.47u	3	
1u	3	
10u	3	
100u	3	

Area allocations shown to relative scale:

Review from Last Time

# Is a capacitor of 1.5fF small enough to be neglected?

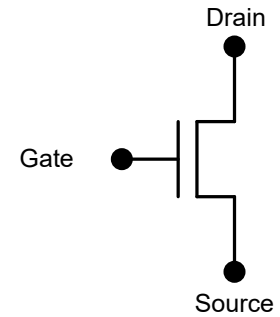


**Area allocations shown to relative scale:**

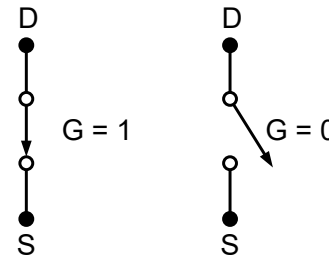
- Not enough information at this point to determine whether this very small capacitance can be neglected
- Will answer this important question later

# Review from Last Time

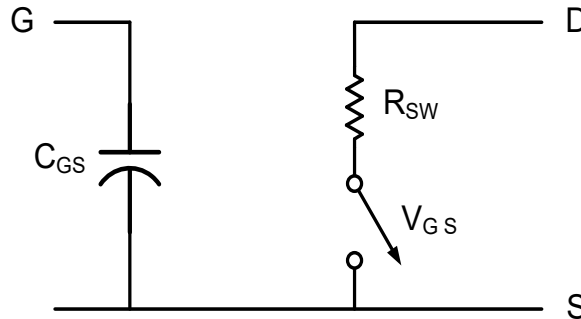
# Model Summary (for n-channel)



## 1. Switch-Level model



## 2. Improved switch-level model



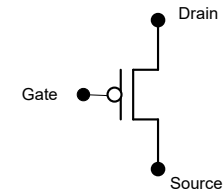
**Switch closed for  $V_{GS} = \text{large}$**   
**Switch open for  $V_{GS} = \text{small}$**

**Other models will be developed later**

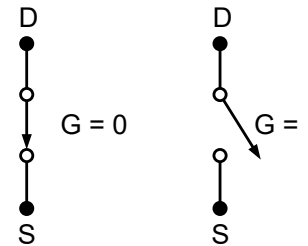


# Review from Last Time

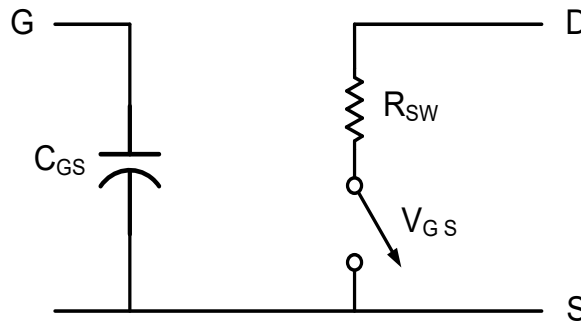
# Model Summary (for p-channel)



## 1. Switch-Level model



## 2. Improved switch-level model



**Switch closed for  $|V_{GS}| = \text{large}$**   
**Switch open for  $|V_{GS}| = \text{small}$**

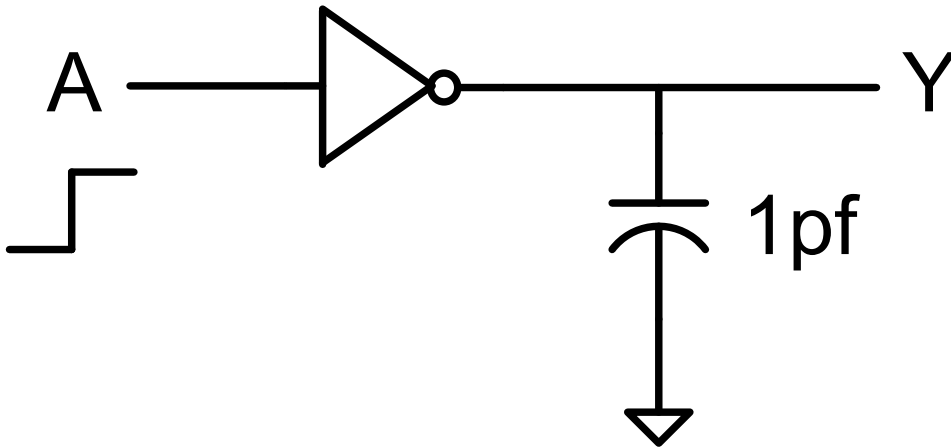
**Other models will be developed later**

# Propagation Delay

# Example

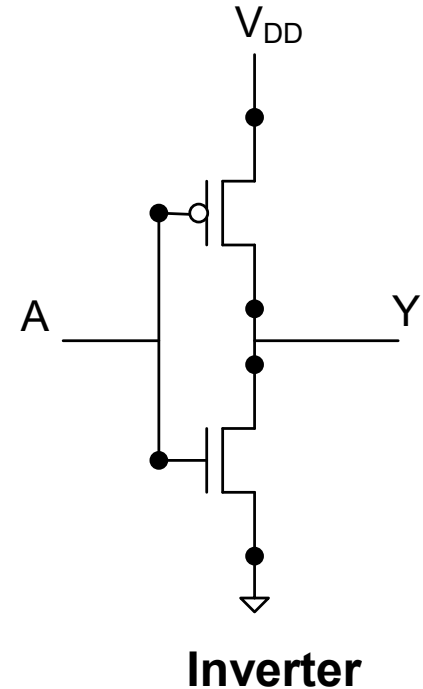
*What are  $t_{HL}$  and  $t_{LH}$ ?*

*Assume  $V_{DD}=5V$*

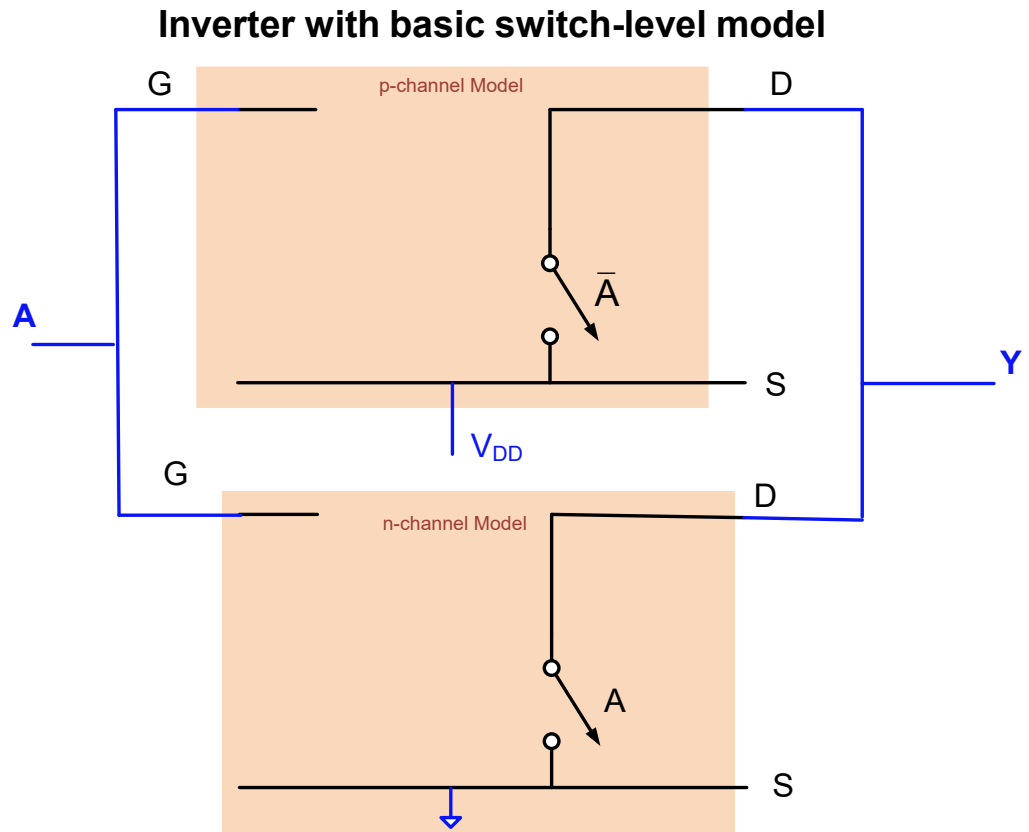
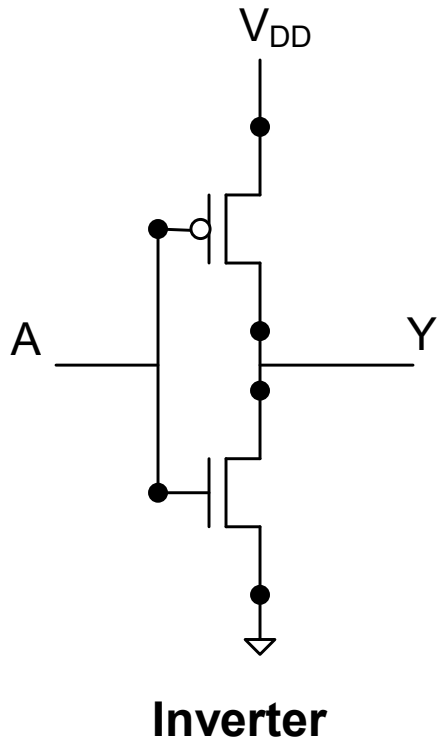


*With basic switch level model ?*

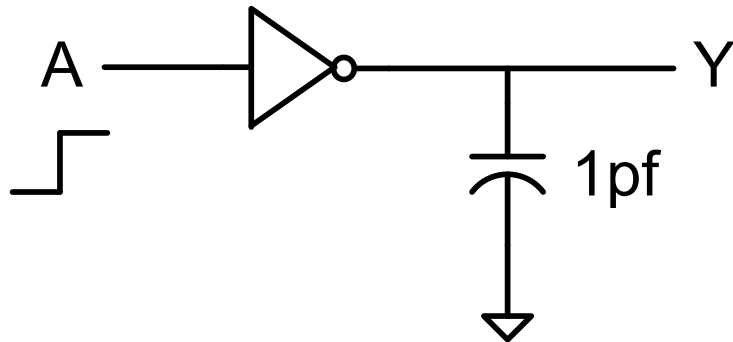
*With improved switch level model ?*



# Example

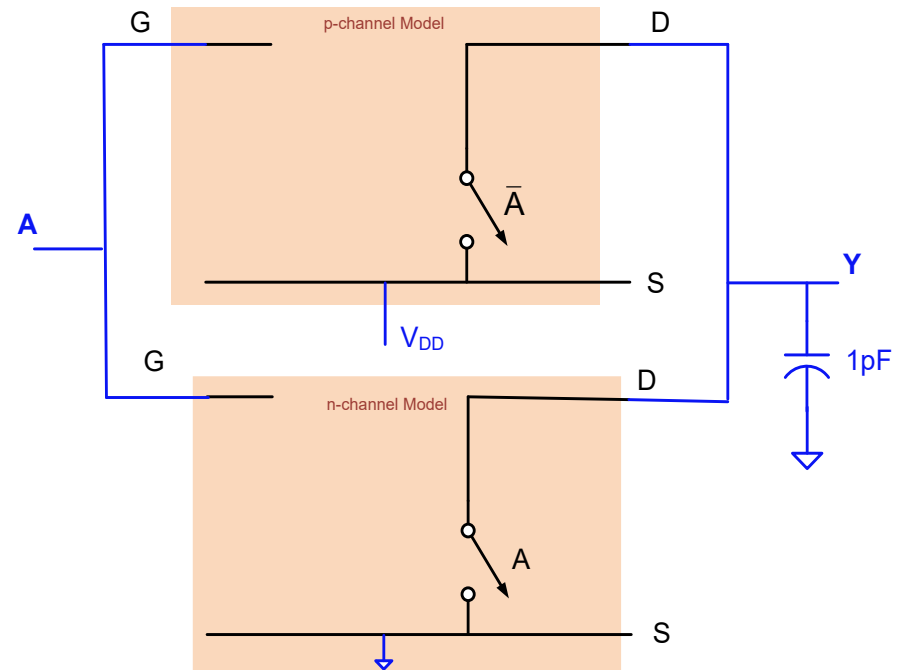
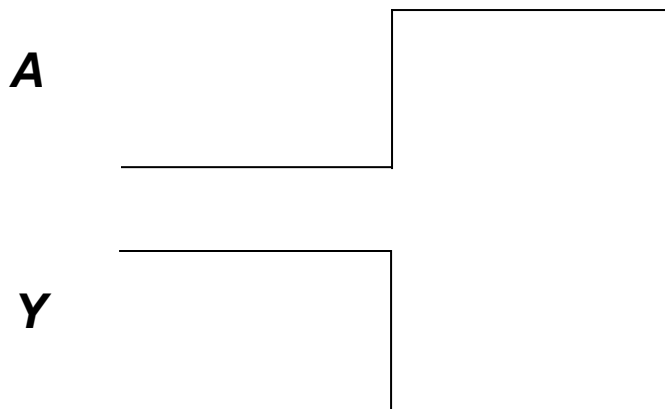


# Example *What are $t_{HL}$ and $t_{LH}$ at output?*



**Assume ideal step at A input**

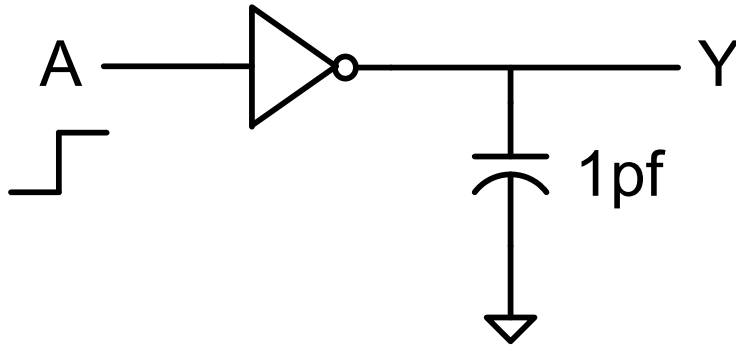
***With basic switch level model***



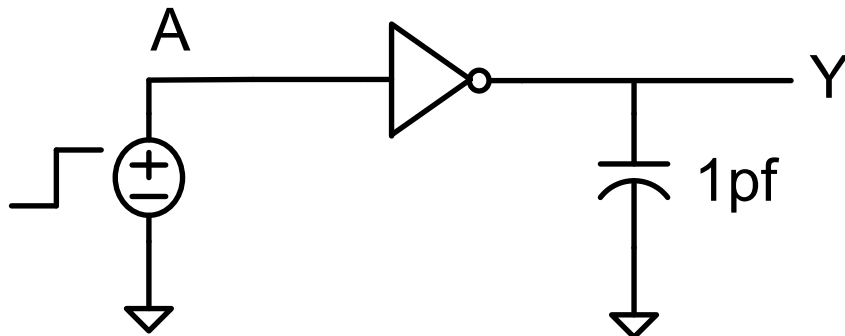
$$t_{HL} = t_{LH} = 0$$

## Example (cont)

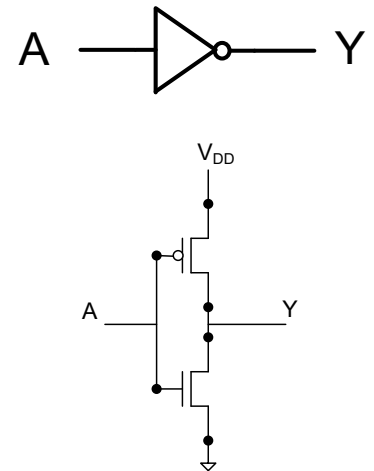
*With simple switch-level model*  $t_{HL} = t_{LH} = 0$



*With improved model ?*



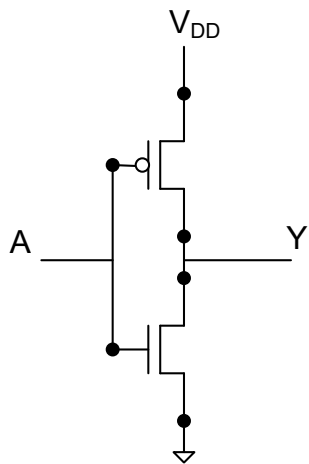
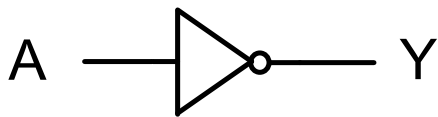
*Inverter Model?*



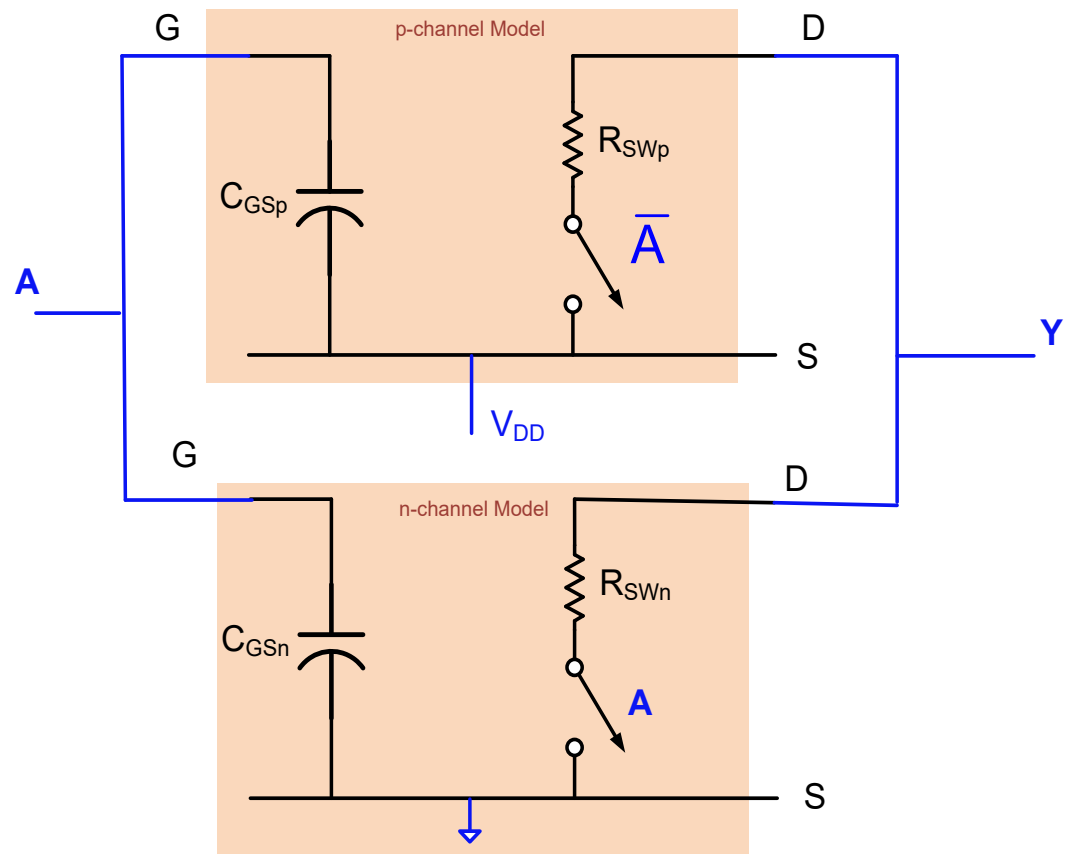
# Example (cont)

## *Inverter with improved model*

### *Inverter Model*

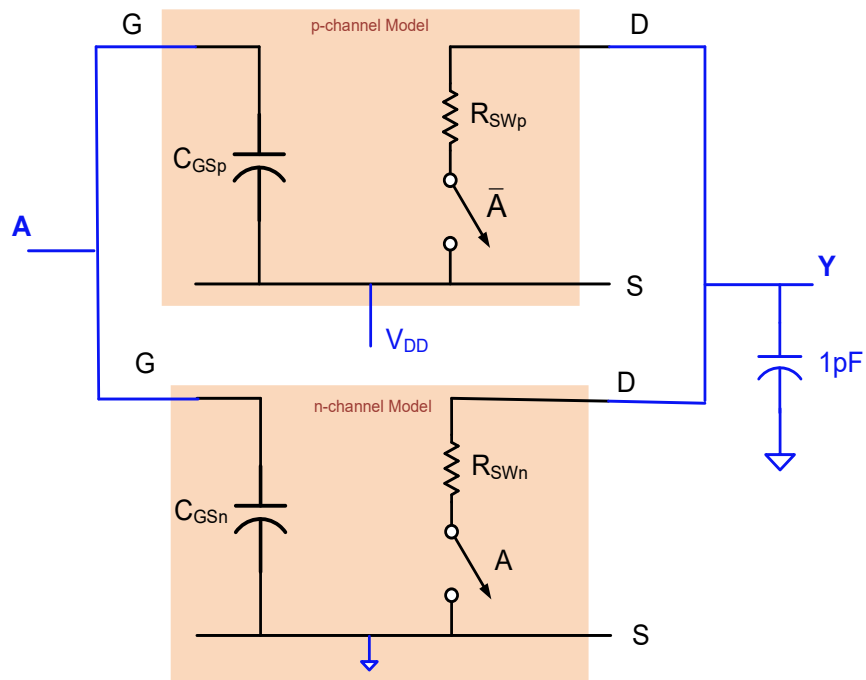
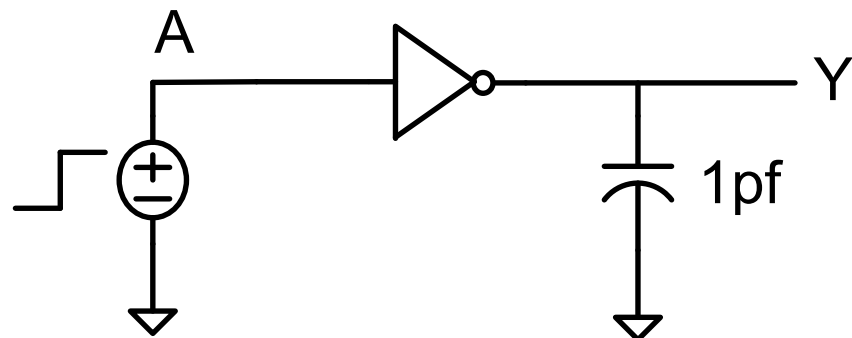


### **Inverter with Improved Model**

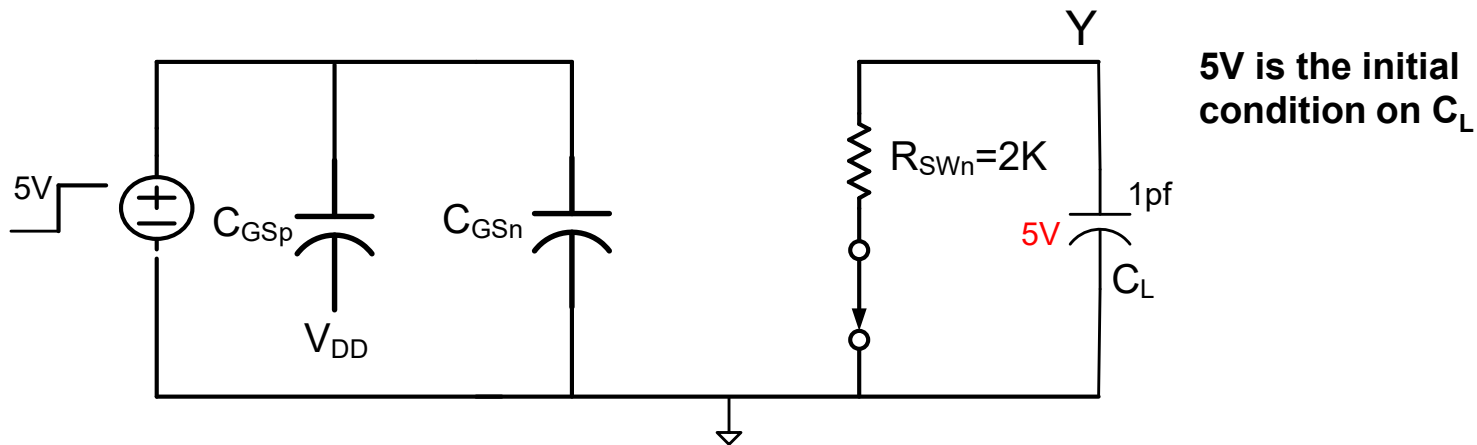


# Example (cont)

With improved model  $t_{HL}=?$



To initiate a HL output transition, assume Y has been in the high state for a long time and lower switch closes at time  $t=0$

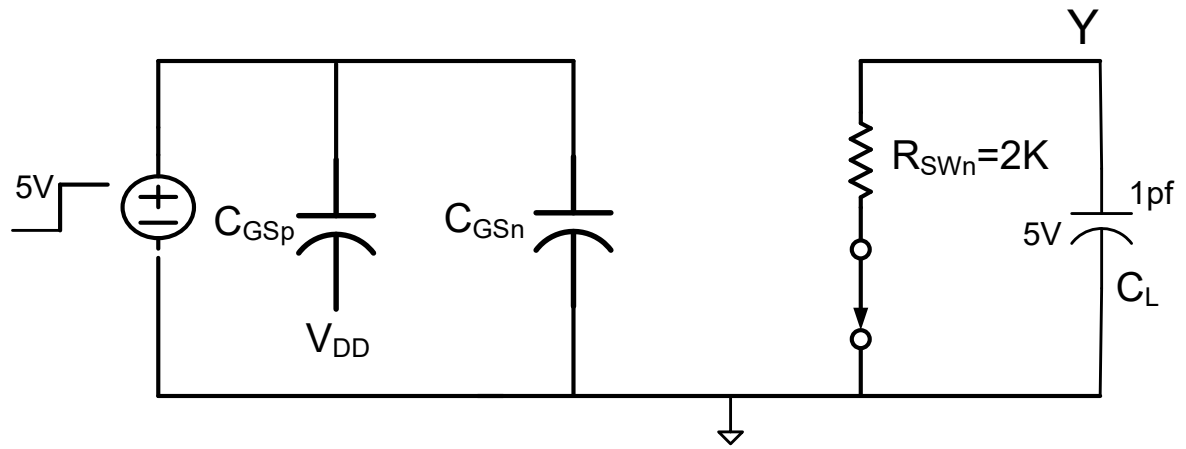




## Example (cont)

*With improved model*

$$t_{HL}=?$$



***Recognize circuit as a first-order RC network***

***Recall: Step response of any first-order network with LHP pole can be written as***

$$y(t) = F + (I - F)e^{-\frac{t}{\tau}}$$

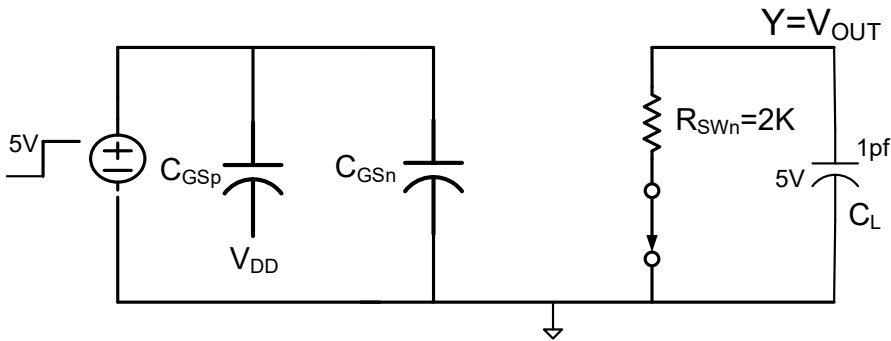
***where  $F$  is the final value,  $I$  is the initial value and  $\tau$  is the time constant of the circuit***

(from Chapter 7 of Nilsson and Riedel)

***For the circuit above,  $F=0$ ,  $I=5$  and  $\tau = R_{SWn} C_L$***

# Example (cont)

*With improved model*

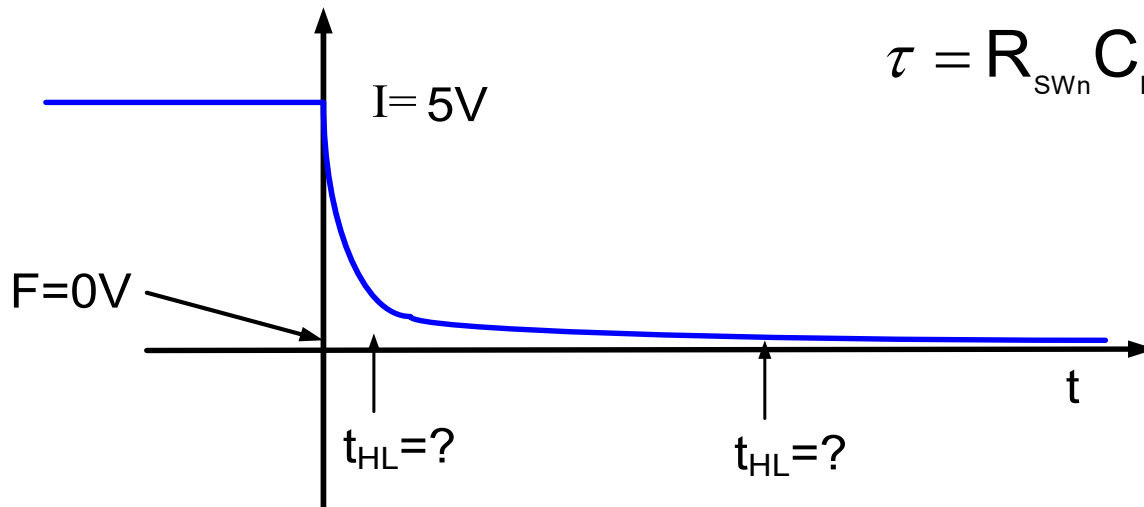


$$t_{HL}=?$$

$$V_{OUT}(t) = F + (I - F)e^{-\frac{t}{\tau}}$$

$$V_{OUT}(t) = 5e^{-\frac{t}{\tau}}$$

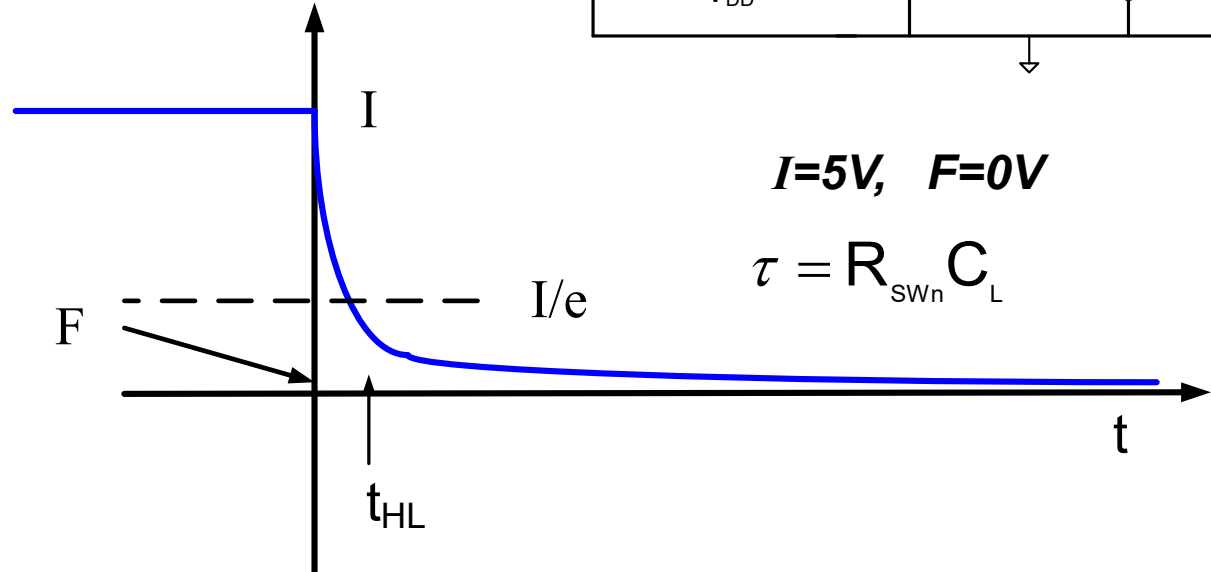
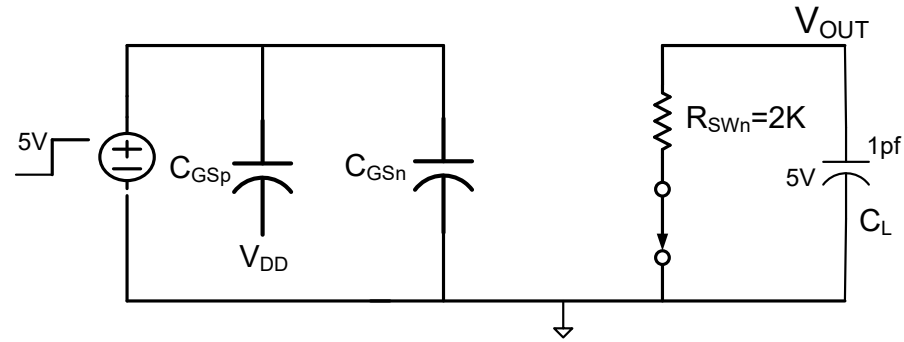
$$\tau = R_{SWn} C_L$$



**how is  $t_{HL}$  defined?**

Example (cont)

$t_{HL}=?$



Define  $t_{HL}$  to be the time taken for output to drop to  $I/e$

$$V_{OUT}(t) = F + (I - F)e^{-\frac{t}{\tau}} \quad \longrightarrow \quad \frac{I}{e} = F + (I - F)e^{-\frac{t_{HL}}{\tau}}$$

Is this simply a mathematical definition or does it have some practical significance?

$t_{HL}$  as defined here and as verified by experimental verification has proven useful at analytically predicting response time of circuits

## Example (cont)

*With improved model*

$$\frac{I}{e} = F + (I - F)e^{-\frac{t_{HL}}{\tau}}$$

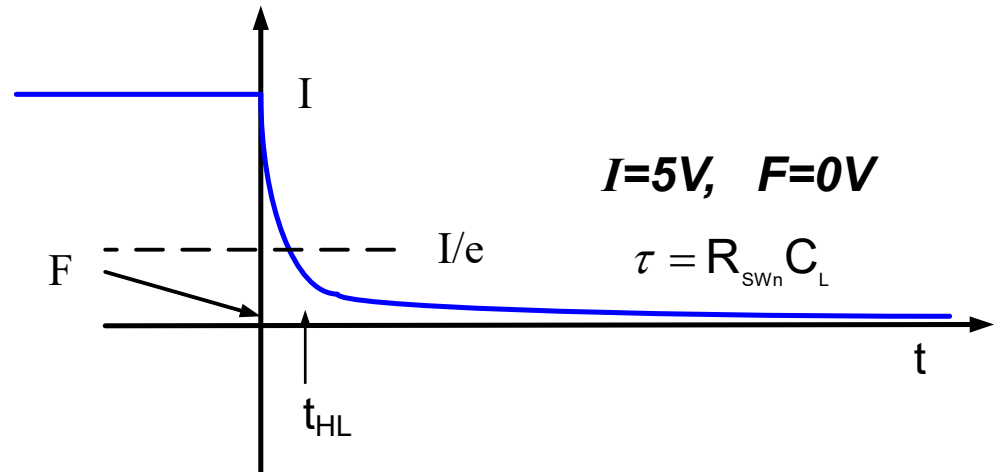
$$\frac{I}{e} = Ie^{-\frac{t_{HL}}{\tau}}$$

$$\frac{1}{e} = e^{-\frac{t_{HL}}{\tau}}$$

$$t_{HL} = \tau$$



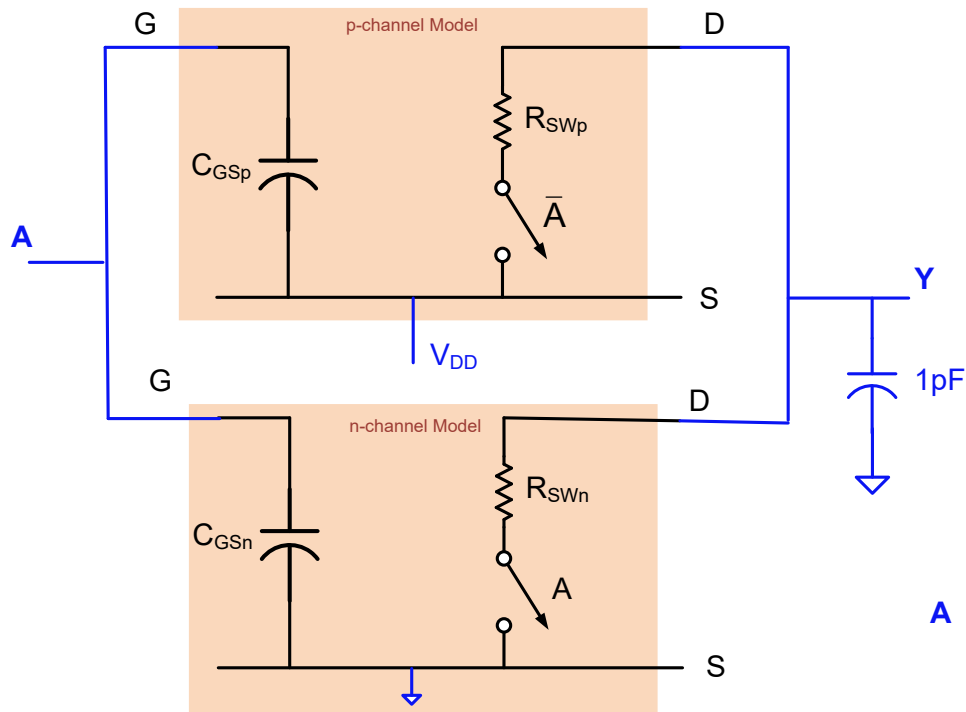
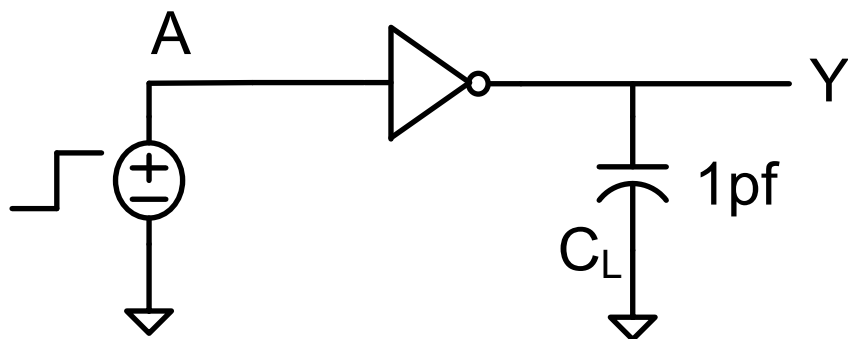
$$t_{HL} = R_{SWn} C_L$$



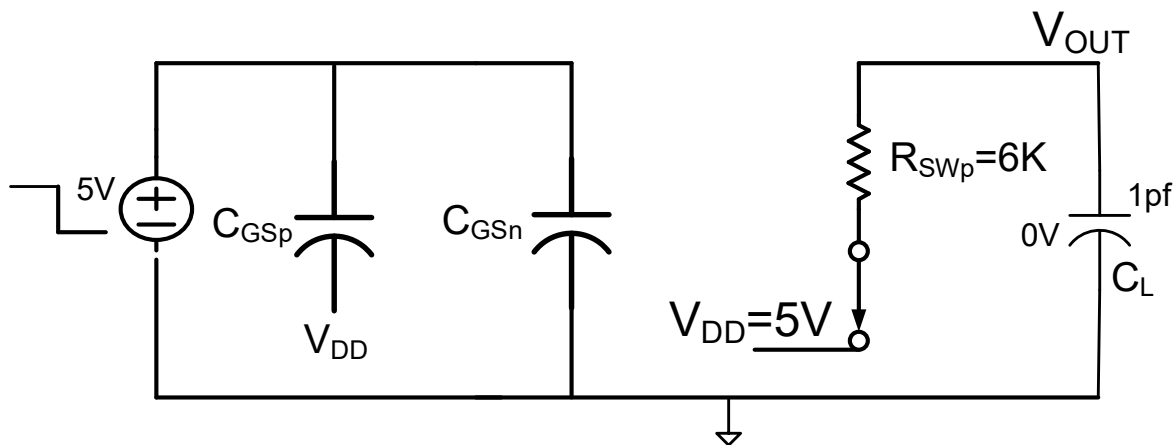
**Both experimental results and accurate computer simulations show that this reasonably accurately predicts how quickly following stages recognize that a logic transition has taken place !!**

# Example (cont)

With improved model  $t_{LH}=?$



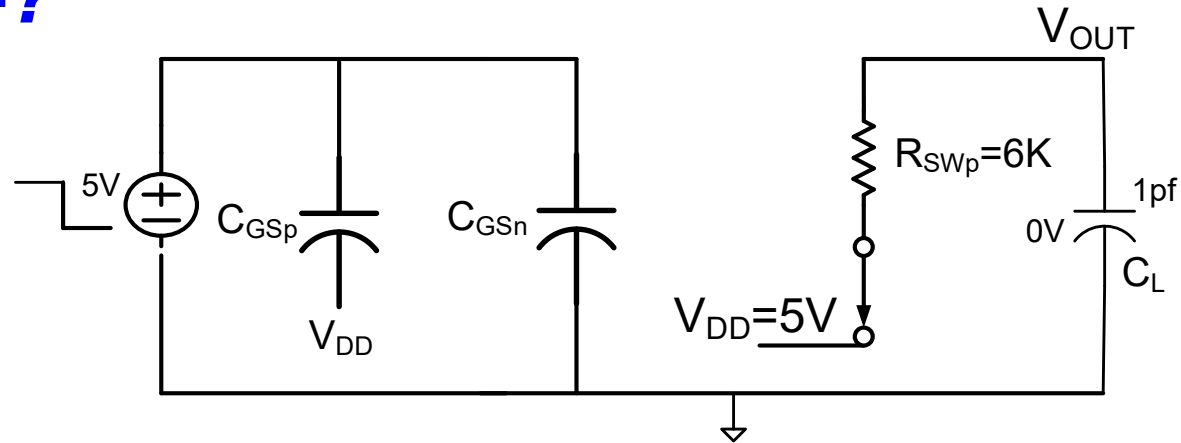
Assume output in low state for a long time and upper switch closes at time  $t=0$



0V is the initial condition on  $C_L$

## Example (cont)

With improved model  $t_{LH}=?$

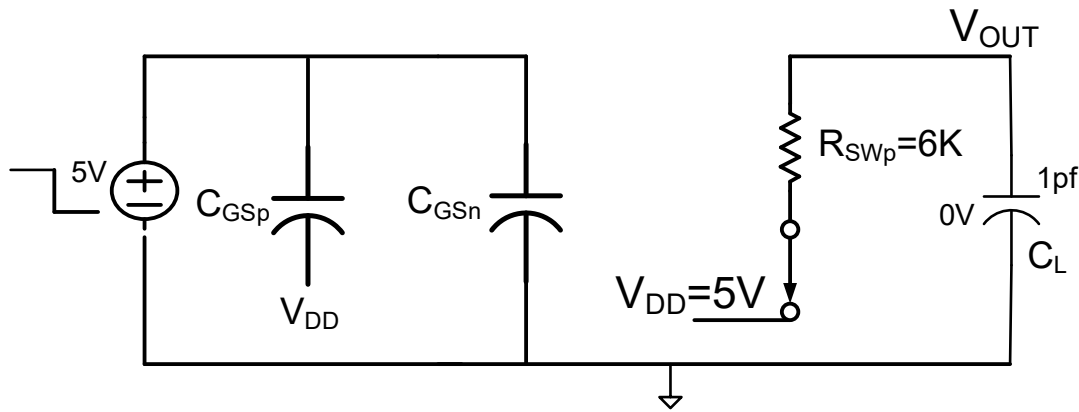


$$y(t) = F + (I - F)e^{-\frac{t}{\tau}}$$

For this circuit,  $F=5$ ,  $I=0$  and  $\tau = R_{swp} C_L$

# Example (cont)

*With improved model*

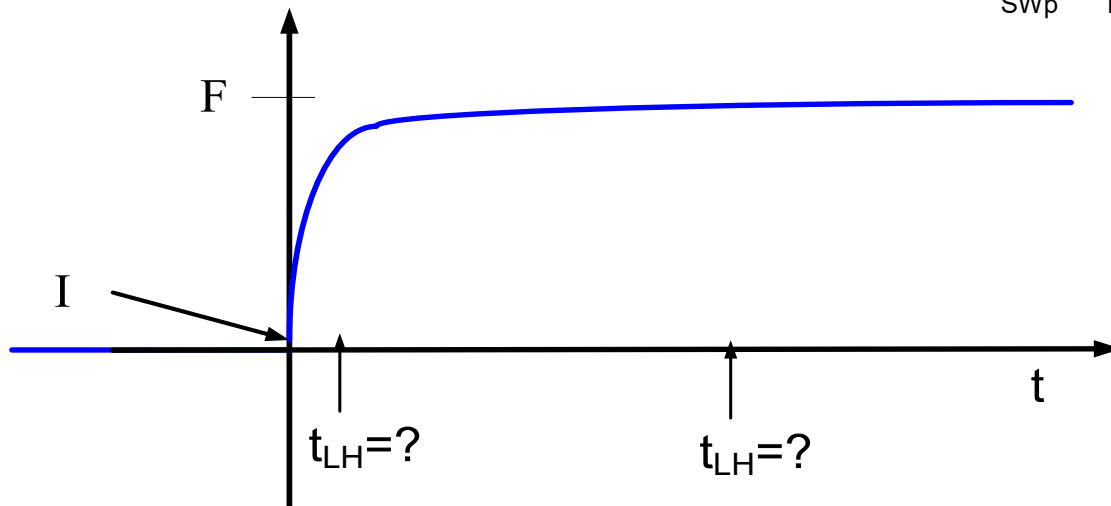


$$t_{LH}=?$$

$$V_{OUT}(t) = F + (I - F)e^{-\frac{t}{\tau}}$$

$$V_{OUT}(t) = 5\left(1 - e^{-\frac{t}{\tau}}\right)$$

$$\tau = R_{SWp} C_L$$



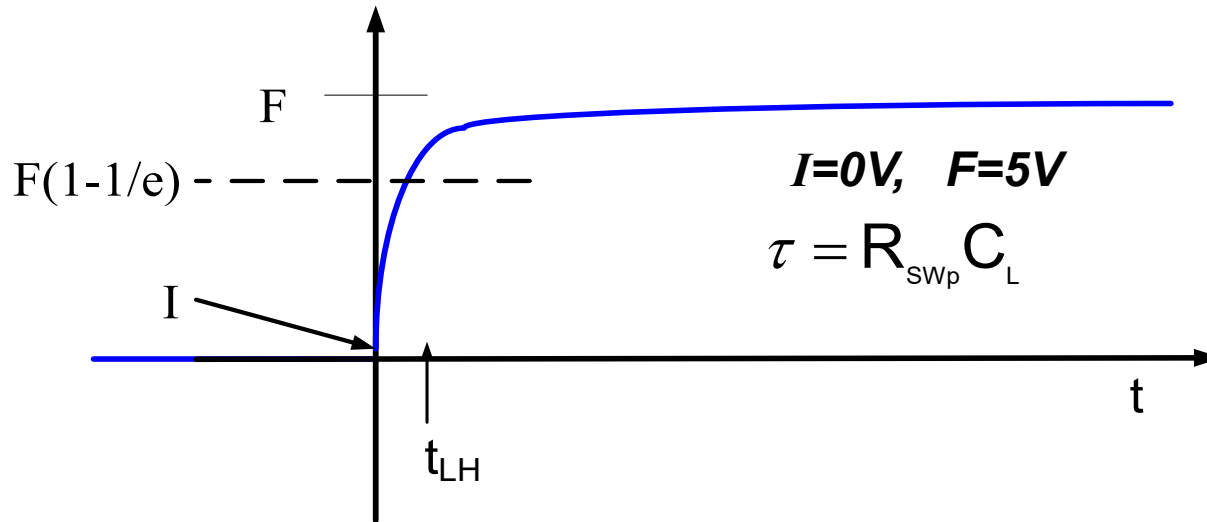
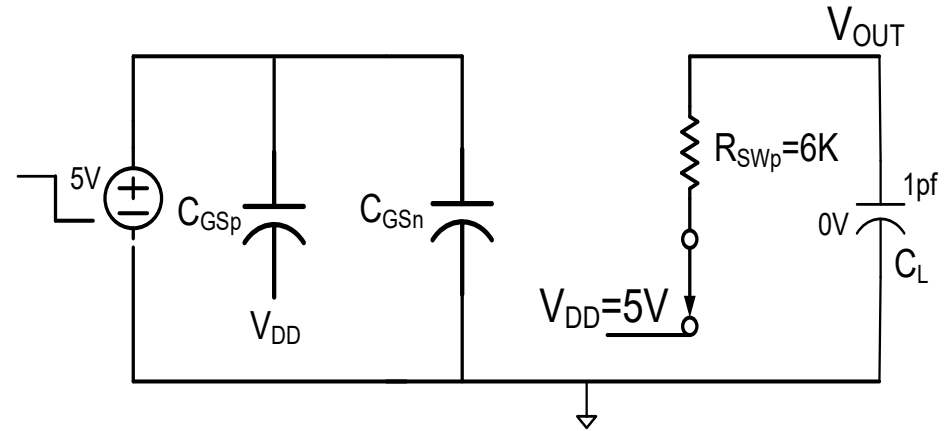
**how is  $t_{LH}$  defined?**

## Example (cont)

With improved model

$t_{LH}=?$

Define  $t_{LH}$  as shown on figure



$t_{LH}$  as defined has proven useful for analytically predicting response time of circuits

$$V_{OUT}(t) = F + (I - F)e^{-\frac{t}{\tau}} \quad \longrightarrow \quad F\left(1 - \frac{1}{e}\right) = F + (I - F)e^{-\frac{t_{LH}}{\tau}}$$



## Example (cont)

With improved model

$$t_{LH}=?$$

$$F\left(1 - \frac{1}{e}\right) = F + (I - F)e^{-\frac{t_{LH}}{\tau}}$$

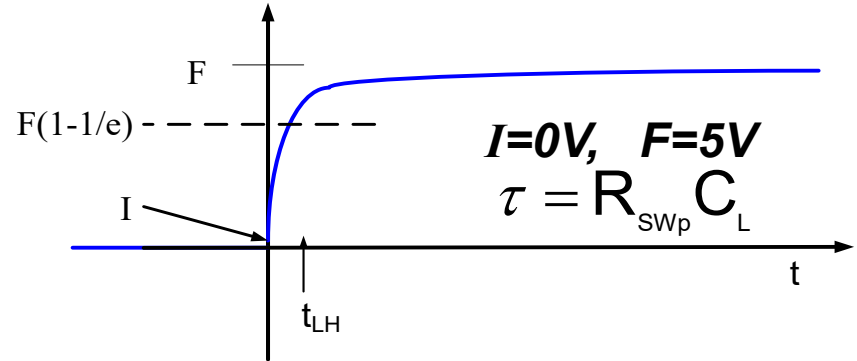
$$F\left(1 - \frac{1}{e}\right) = F + (F)e^{-\frac{t_{LH}}{\tau}}$$

$$1 - \frac{1}{e} = 1 + e^{-\frac{t_{LH}}{\tau}}$$

$$t_{LH} = \tau$$

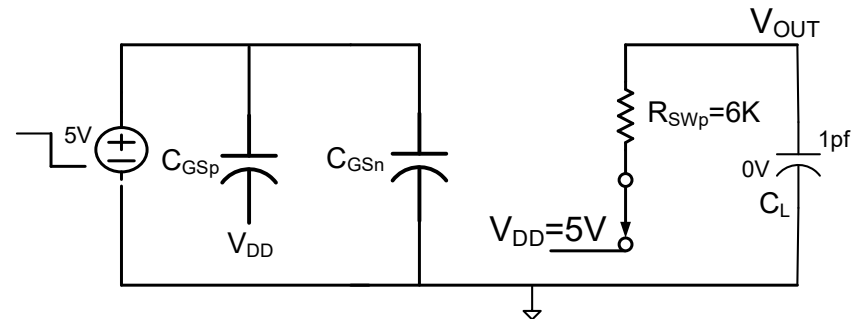
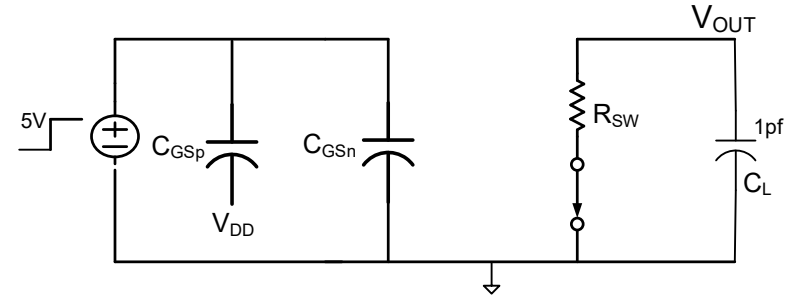


$$t_{LH} = R_{SWp} C_L$$



## Example (cont)

*With improved model*



$$t_{HL} \cong R_{SWn} C_L$$

In the ON 0.5u process  
 $= 2K \bullet 1pF = 2n \text{ sec}$

$$t_{LH} \cong R_{SWp} C_L$$

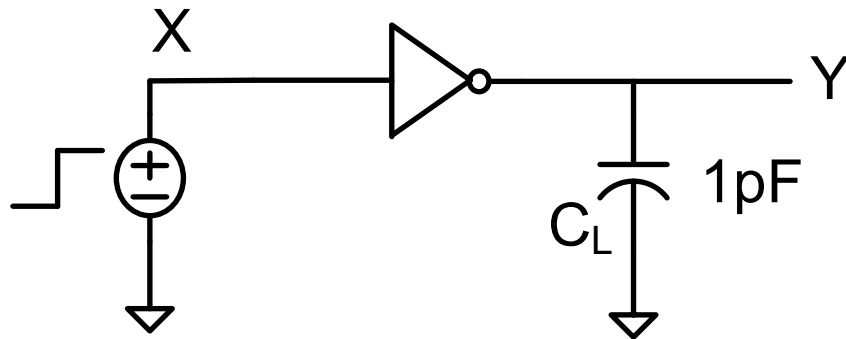
$$= 6K \bullet 1pF = 6n \text{ sec}$$

***Note this circuit is quite fast !***

***Note that  $t_{HL}$  is much shorter than  $t_{LH}$***

***Often  $C_L$  will be even smaller and the circuit will be much faster !!***

Summary: What is the delay of a minimum-sized inverter driving a 1pF load?

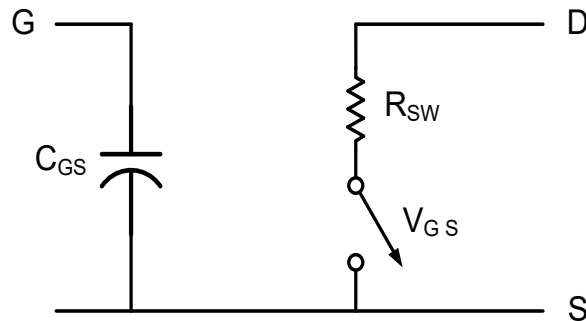
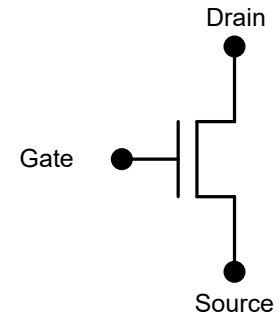


In the ON 0.5 $\mu$  process

$$t_{HL} \cong R_{SWn} C_L = 2K \bullet 1pF = 2n \text{ sec}$$

$$t_{LH} \cong R_{SWp} C_L = 6K \bullet 1pF = 6n \text{ sec}$$

# Improved switch-level model



Switch closed for  $V_{GS} = \text{large}$

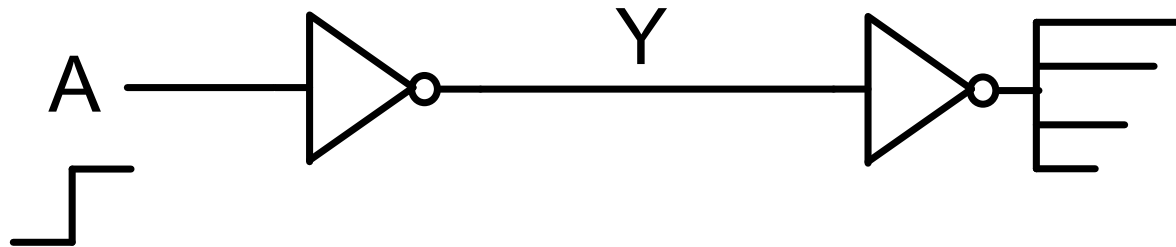
Switch open for  $V_{GS} = \text{small}$

- Previous example showed why  $R_{sw}$  in the model was important
- But of what use is the  $C_{GS}$  which did not enter the previous calculations?

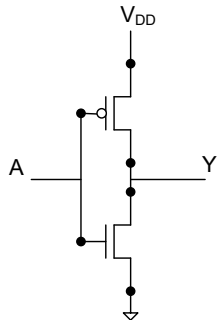
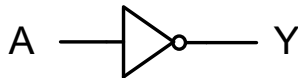
For minimum-sized devices in a  $0.5\mu$  process

$$C_{GS} \cong 1.5\text{fF} \quad R_{sw} \cong \left. \begin{array}{l} 2\text{K}\Omega \text{ n-channel} \\ 6\text{K}\Omega \text{ p-channel} \end{array} \right\}$$

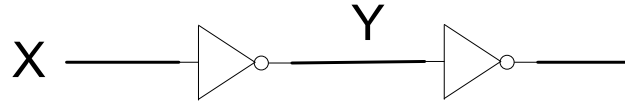
***One gate often drives one or more other gates !***



***What are  $t_{HL}$  and  $t_{LH}$ ?***

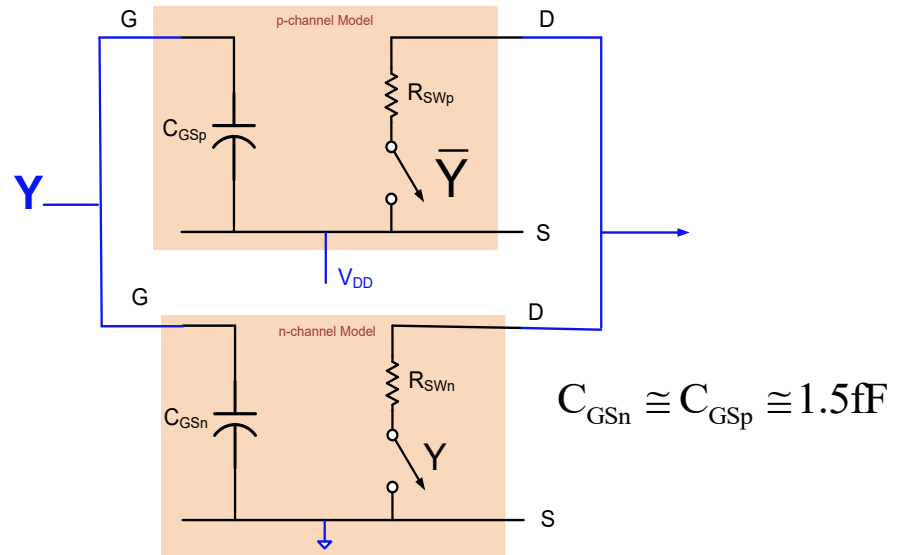


Example: What is the delay of a minimum-sized inverter driving another identical device?

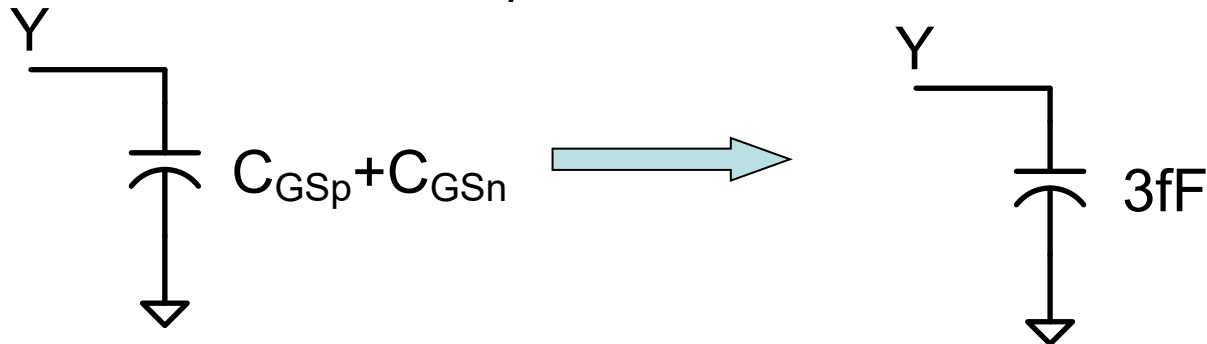


Load on first inverter

$C_{GSn}$  and  $C_{GSp}$  both 1.5fF

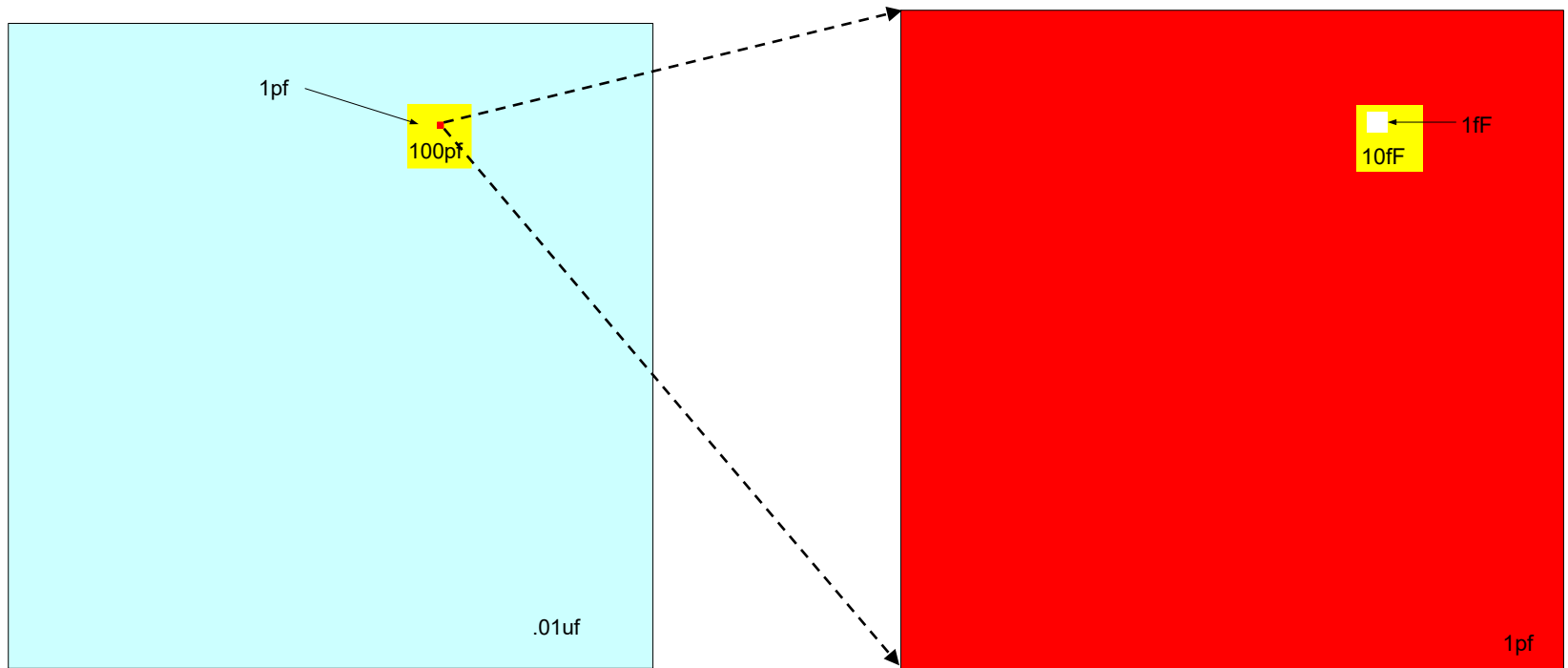


Loading effects same whether  $C_{GSp}$  and/or  $C_{GSn}$  connected to  $V_{DD}$  or GND



For convenience, will reference both to ground

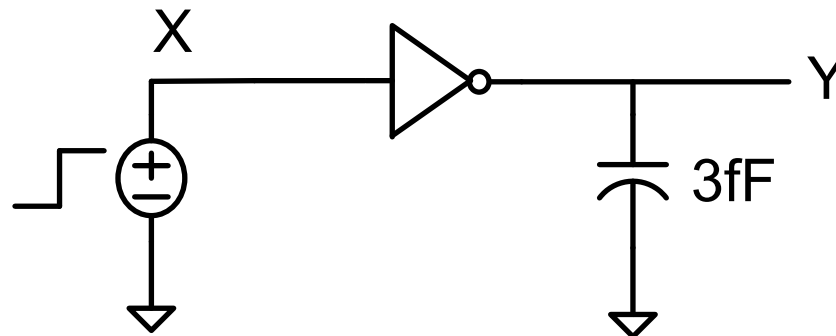
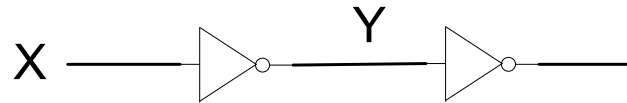
# Is a capacitor of 1.5fF small enough to be neglected?



**Area allocations shown to relative scale:**

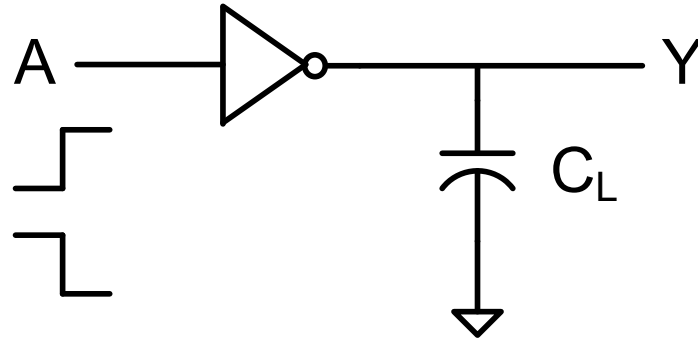
- This example will provide insight into the answer of the question

Example: What is the delay of a minimum-sized inverter driving another identical device? Assume  $V_{DD}=5V$





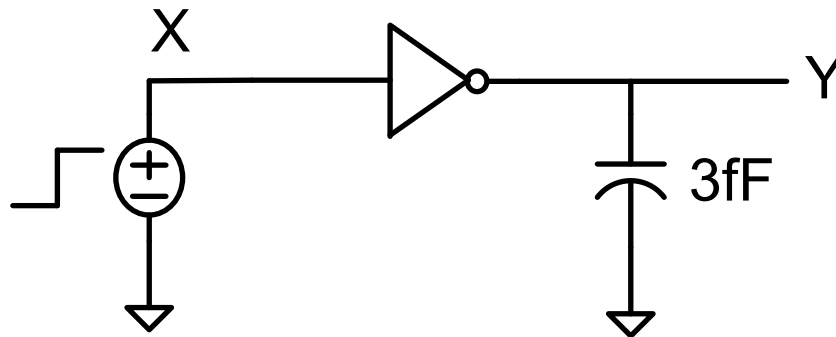
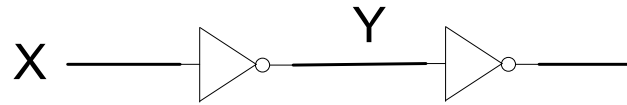
# Generalizing the Previous Analysis to Arbitrary Load



$$t_{HL} \cong R_{SWn} C_L$$

$$t_{LH} \cong R_{SWp} C_L$$

Example: What is the delay of a minimum-sized inverter driving another identical device?



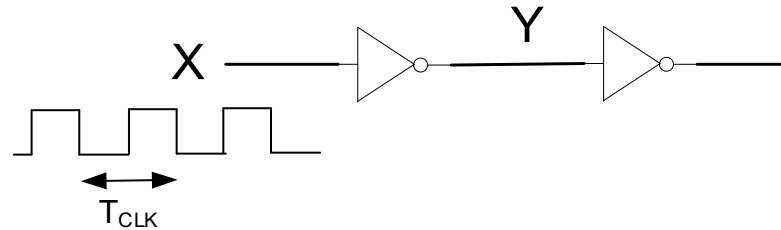
$$t_{HL} \cong R_{SWn} C_L = 2K \bullet 3fF = 6p \text{ sec}$$

$$t_{LH} \cong R_{SWp} C_L = 6K \bullet 3fF = 18p \text{ sec}$$

Do gates really operate this fast?

What would be the maximum clock rate for acceptable operation?

Example: What is the delay of a minimum-sized inverter driving another identical device?



$$t_{HL} \cong R_{SWn} C_L = 6 \text{ p sec}$$

$$t_{LH} \cong R_{SWp} C_L = 18 \text{ p sec}$$

What would be the maximum clock rate for acceptable operation?

$$T_{CLK\text{-min}} = t_{HL} + t_{LH}$$

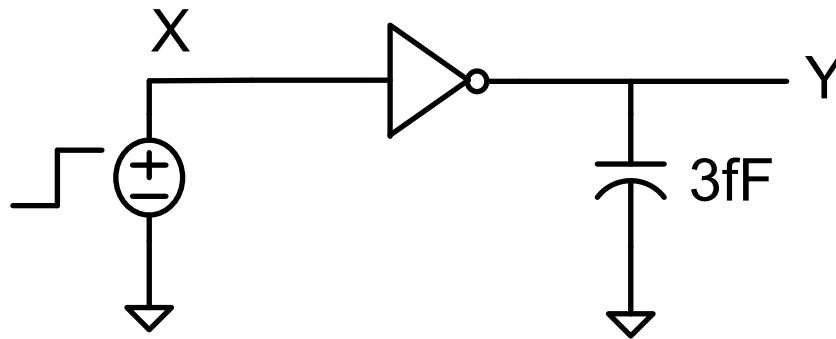
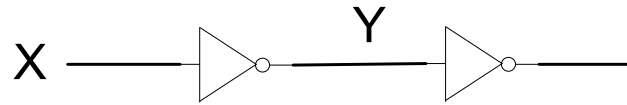
$$f_{CLK\text{-max}} = \frac{1}{T_{CLK\text{-min}}} = \frac{1}{24 \text{ psec}} = 40 \text{ GHz}$$

And much faster in a finer feature process !!

??????

What would be the implications of allowing for 10 levels of logic and 10 loads (FanOut=10)?

Example: What is the delay of a minimum-sized inverter driving another identical device? SUMMARY

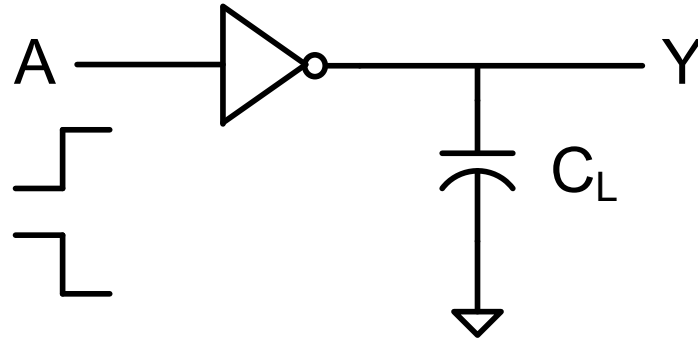


$$t_{HL} \cong R_{SWn} C_L = 2K \bullet 3fF = 6p \text{ sec}$$

$$t_{LH} \cong R_{SWp} C_L = 6K \bullet 3fF = 18p \text{ sec}$$

*This is very fast but even the small 1.5fF capacitors are not negligible !  
These capacitors play a key role in determining the speed of a circuit !*

## Response time of logic gates



$$t_{HL} \cong R_{SWn} C_L$$

$$t_{LH} \cong R_{SWp} C_L$$

- Logic Circuits can operate very fast
- Extremely small parasitic capacitances play key role in speed of a circuit

# Some Observations about Technology and Politics

Technology discussions and laboratory designs in this course will be in an ON 0.5 $\mu$ m process

This technology was State of the Art in about 1995 (25 years ago!)

State of the Art today is about 7nm

Technology Evolution:

5 $\mu$ m, 3 $\mu$ m, 1 $\mu$ m, 0.5 $\mu$ m, 0.35 $\mu$ m, 0.5 $\mu$ m, 0.18  $\mu$ m , 0.1 $\mu$ m, 90nm, 65nm, 45nm, 28nm, 22nm, 14nm, 10nm, 7nm, 5nm

11 generations since the 0.5 $\mu$ m process was at the State of the Art

When 0.5 $\mu$ m processes were state of the art, most US researchers and most universities were working with the state of the art processes or maybe one generation behind the state of the art

# Some Observations about Technology and Politics

## Technology Evolution:

5 $\mu$ m, 3 $\mu$ m, 1 $\mu$ m, 0.5 $\mu$ m, 0.35 $\mu$ m, 0.5 $\mu$ m, 0.18  $\mu$ m , 0.1 $\mu$ m, 90nm, 65nm,  
45nm, 28nm, 22nm, 14nm, 10nm, 7nm, 5nm

Students at universities in Asia and Europe often have ready access to technologies in the 14nm to 28nm realm and sometimes even finer

Are we using obsolete technology in US Universities Today?

Why do we not have ready access to “state of the art” technologies in US Universities?

Will students trained with 25 year old technologies be able to work with state of the art technologies?

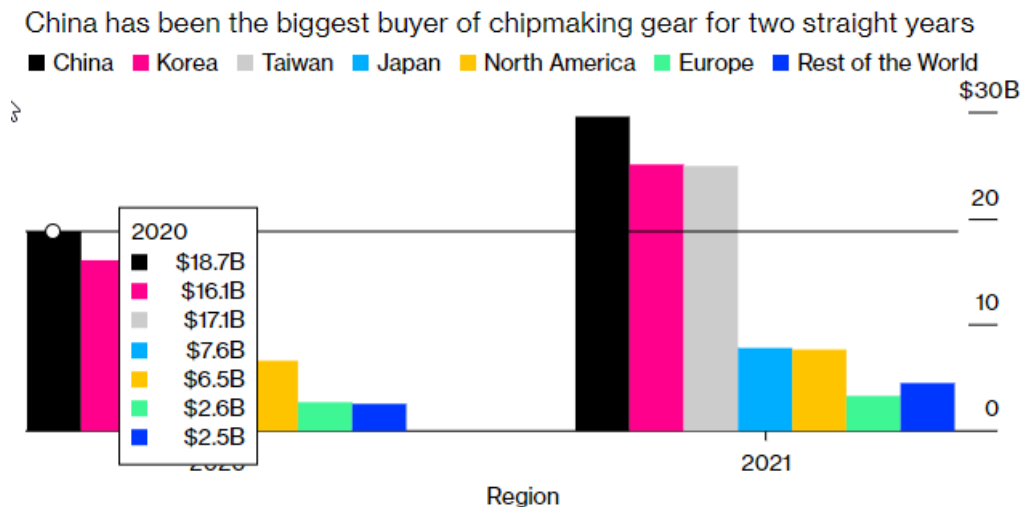
Are the larger feature size technologies still used by industry today in the US or abroad?

# Some Observations about Technology and Politics

Are the larger feature size technologies still used by industry today in the US or abroad?

GlobalData predicts that the Chinese market will play a much smaller role for foreign suppliers by 2030. More than 90% of the chips sold and used worldwide involve low-process production technology.

<https://www.investmentmonitor.ai/analysis/china-lead-global-semiconductor-growth-2030#:~:text=Global%20semiconductor%20industry%20revolves%20around,Samsung%20Electronics%20and%20SK%20Hynix.>



Source: SEMI



# Some Observations about Technology and Politics

Sept 2022

<https://technode.com/2021/03/04/where-china-is-investing-in-semiconductors-in-charts/>

China is the world's largest consumer of semiconductors, and the lion's share of revenue from purchasing these chips go to foreign firms. China consumed \$143.4 billion worth of wafers in 2020, and just 5.9% of them were produced by companies headquartered in China.

# Some Observations about Technology and Politics

US Government has recognized that investment in the semiconductor industry is critical to regain technical dominance in the field

The US is now in a serious catchup position because except for Intel, US technology is now more than a decade behind foreign competitors

**A recent announcement looks promising for the future !**

<https://www.washingtonpost.com> › 2021/06/14 › global... ⋮

Senate approved \$52 billion in subsidies for chip manufacturing

This is now a one-time initiative presumably spread over several years

**Will this investment close the gap that exists today in semiconductor technology and actually reverse the world order in the semiconductor industry?**

**Is this a well-recognized mandate?**

The U.S. Senate on Tuesday voted 68-32 in favor of legislation i

# Some Observations about Technology and Politics

THE WHITE HOUSE



BRIEFING ROOM

## FACT SHEET: CHIPS and Science Act Will Lower Costs, Create Jobs, Strengthen Supply Chains, and Counter China

D

**Spurred by the passage of the CHIPS and Science Act of 2022, this week, companies have announced nearly \$50 billion in additional investments in American semiconductor manufacturing, bringing total business investment to nearly \$150 billion since President Biden took office:**

# Some Observations about Technology and Politics

## August 2022:

↳

- Micron is announcing a **\$40 billion** investment in memory chip manufacturing, critical for computers and electronic devices, which will create up to 40,000 new jobs in construction and manufacturing. This investment alone will bring the U.S. market share of memory chip production from less than 2 percent to up to 10 percent over the next decade.
- Qualcomm and GlobalFoundries are announcing a new partnership that includes **\$4.2 billion** to manufacture chips in an expansion of GlobalFoundries' upstate New York facility. Qualcomm, the leading fabless semiconductor company in the world, announced plans to increase semiconductor production in the U.S. by up to 50 percent over the next five years.

# Some Observations about Technology and Politics

**Will this \$52 Billion investment by US Government close the gap that exists today in semiconductor technology or actually reverse the world order in the semiconductor industry?**

When Pat Gelsinger, the chief executive of U.S. chip giant Intel, visited Europe this spring to scout potential locations for a new factory, officials rolled out the red carpet. European nations are aiming to use part of a 145 billion euro digital fund — about \$175 billion — to finance chip investments and double [their share of worldwide chip manufacturing](#) by 2030, to 20 percent of the \$540 billion global market.

<https://www.reuters.com> › [technology](#) › [taiwan-minister-s...](#) ⋮

[Taiwan's chip industry set for years of growth: minister | Reuters](#)

Apr 23, 2021 — He said between now and 2025, **Taiwan** companies have planned more than T\$3 trillion (\$107 billion) in **investment** in the **semiconductor** sector, ...

# Some Observations about Technology and Politics

**Will this \$52 Billion investment by US Government close the gap that exists today in semiconductor technology or actually reverse the world order in the semiconductor industry?**

<https://www.industryweek.com> › article › taiwans-tsmc-... ⋮

## Taiwan's TSMC Plans \$100 Billion Investment to Meet Demand

Apr 5, 2021 — **Taiwan Semiconductor** Manufacturing Company said Thursday it was planning to **invest** \$100 billion over the next three years to meet soaring ...

South Korea became the latest country to announce a colossal investment in the industry last week. The nation's government said Thursday that **510 trillion South Korean won (\$452 billion)** will be invested in chips by 2030, with the bulk of that coming from private companies in the country. *May 17, 2021*

Samsung Group, South Korea's tech giant, announced on Tuesday that it will invest **\$205 billion (240 trillion won)** in their semiconductor, biopharmaceuticals and telecommunications units over the next three years to enhance its global presence and lead in new industries such as next-generation telecommunication and ... *Aug 24, 2021*

# Some Observations about Technology and Politics

**Will this \$52 Billion investment by US Government close the gap that exists today in semiconductor technology or actually reverse the world order in the semiconductor industry?**

<https://thediplomat.com> › [2020/09](#) › [can-china-become...](#) ⋮

## Can China Become the World Leader in Semiconductors?

Sep 25, 2020 — **China** appears on track to reach the **investment** level of \$150 billion in 2020 without having reached either of its stated long-term goals. And ...

# Some Observations about Technology and Politics

Will this \$52 Billion investment by US Government close the gap that exists today in semiconductor technology or actually reverse the world order in the semiconductor industry?

## Summary of Reported Investments by Some Key Players

Timeframes of investments vary making comparisons sketchy

<b>US Government</b>	<b>\$50 Billion</b>
<b>Intel</b>	<b>\$100 Billion (over 10 years ?)</b>
<b>Micron</b>	<b>\$40 Billion</b>
<b>Qualcomm &amp; GlobalFoundries</b>	<b>\$4.2 Billion</b>
<b>European Governments</b>	<b>\$175 Billion</b>
<b>Taiwan Government</b>	<b>\$107 Billion</b>
<b>TSMC</b>	<b>\$100 Billion</b>
<b>Korean Government</b>	<b>\$450 Billion</b>
<b>Samsung (included?)</b>	<b>\$205 Billion</b>
<b>China</b>	<b>\$150 Billion (in 2020 alone)</b>



# Some Observations about Technology and Politics

**There are serious concerns in the US military that the US will not be able to maintain state of the art military systems without domestic state of the art semiconductor technology**

**The lack of access to state of the art semiconductor technologies in most US universities is primarily driven by the lack of commitment by the US government to support these programs and to support the semiconductor industry to the level of support provided in some other countries**

**Input on re-establishing priority for governmental support of the US semiconductor industry is critical**

**Many companies around the world are still using 65nm to 0.5 $\mu$ m technologies for new designs and will for the foreseeable future**

**Extremely high volume applications of highly complex systems operating at high speeds drive the state of the art technologies though the total semiconductor sales from products designed and manufactured in legacy technologies is much larger!**



**Stay Safe and Stay Healthy !**

**End of Lecture 7**